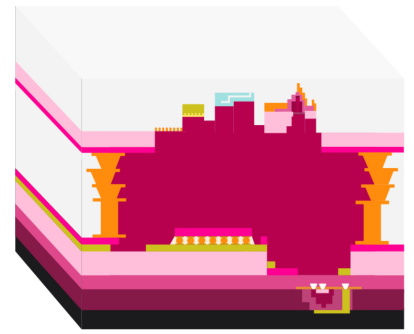


# 4th DWL Workshop

Sydney 2 Feb 2026



## Registration open for: DWL Workshop and Webinar Series

The **4th DWL Workshop**, proudly sponsored by ANFF, will be held on **Monday, February 2, 2026**, at the University of Sydney. Join researchers, scientists, and micro/nanofabrication experts for this one-day event exploring the latest in direct write lithography (DWL) including electron, photon, ion beam and more! Educational webinars will also begin in November 2025.

### Want to present at the workshop?

We're calling on researchers, scientists, and experts in micro and nanofabrication to share their insights at the "Innovative Research in Direct Write Lithography Workshop." If you're working on new techniques, applications, or advancements in direct write lithography, we want to hear from you. For details on how to submit your abstract, scan the QR code on the right or [click here](#).



### Keynote speaker at the 4<sup>th</sup> DWL Workshop



**Gerald G. Lopez, Ph.D.** Director of Operations and Business & Center Associate Director Singh Center for Nanotechnology  
University of Pennsylvania | MAEBL Co-Founder and Board Chair | EIPBN Operations Trustee

|            | Melb, Syd                 | Adelaide                  | Perth                     | Berlin                   | NY                       | LA                       | Topic / Title                                                                        | Facilitator / Speaker                                   |
|------------|---------------------------|---------------------------|---------------------------|--------------------------|--------------------------|--------------------------|--------------------------------------------------------------------------------------|---------------------------------------------------------|
| <b>W1</b>  | AEDT<br>11:00<br>06.11.25 | ACDT<br>10:30<br>06.11.25 | AWST<br>08:00<br>06.11.25 | CET<br>1:00<br>06.11.25  | EST<br>19:00<br>05.11.25 | PST<br>16:00<br>05.11.25 | 50 Years of Reactive Ion Etching in Microelectronics                                 | Christophe Vallee<br>(University at Albany)             |
| <b>W2*</b> | AEDT<br>16:00<br>27.11.25 | ACDT<br>15:30<br>27.11.25 | AWST<br>13:00<br>27.11.25 | CET<br>6:00<br>27.11.25  | EST<br>0:00<br>27.11.25  | PST<br>21:00<br>26.11.25 | The Physics and Chemistry of Plasma Etching (Part I)                                 | Henri Jansen*<br>(DTU)                                  |
| <b>W3*</b> | AEDT<br>16:00<br>11.12.25 | ACDT<br>15:30<br>11.12.25 | AWST<br>13:00<br>11.12.25 | CET<br>6:00<br>11.12.25  | EST<br>0:00<br>11.12.25  | PST<br>21:00<br>10.12.25 | The Physics and Chemistry of Plasma Etching (Part II)                                | Henri Jansen*<br>(DTU)                                  |
| <b>W4</b>  | AEDT<br>12:00<br>29.01.26 | ACDT<br>11:30<br>29.01.26 | AWST<br>09:00<br>29.01.26 | CET<br>2:00<br>29.01.26  | EST<br>20:00<br>28.01.26 | PST<br>17:00<br>28.01.26 | Atomic Mechanisms During Plasma Etching                                              | David Graves<br>(Princeton University)                  |
| <b>W5</b>  | AEDT<br>tbd<br>.03.26     | ACDT<br>tbd<br>.03.26     | AWST<br>tbd<br>.03.26     | CET<br>tbd<br>.03.26     | EST<br>tbd<br>.03.26     | PST<br>tbd<br>.03.26     | Using the right tool for the job: Comparing ALE, RIE and IBE                         | Nick Chittock<br>(Oxford Instruments Plasma Technology) |
| <b>W6</b>  | AEST<br>11:00<br>08.04.26 | ACST<br>10:30<br>08.04.26 | AWST<br>9:00<br>08.04.26  | CEST<br>3:00<br>08.04.26 | EDT<br>21:00<br>07.04.26 | PDT<br>18:00<br>07.04.26 | Helicon Double Layer Thruster: A radiofrequency plasma source with many applications | Christine Charles<br>(ANU)                              |

\* Please be aware that the webinar you'll be watching is a pre-recorded session. After the presentation, there will be a live Q&A segment.

**SCAN TO REGISTER FOR THE EVENT OR [CLICK HERE](#)**



**+ CONTACT**

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